# UNIVERSITY OF CALIFORNIA, BERKELEY College of Engineering Department of Electrical Engineering and Computer Sciences

EE 105: Microelectronic Devices and Circuits

Fall 2011

Time allotted: 75 minutes						
NAME: _	Solution					
STUDENT	Γ ID#:					
INSTRUC	CTIONS:					
a b c d d 2. SHC	ess otherwise stated, assume temperature is 300 K material is Si No Early effect All capacitors are shorted at the operating frequency  WYOUR WORK. (Make your methods clear to the grader!) Specially, while using chart, make sure that you indicate how you have got your numbers. For example, if reading off mobility, clearly write down what doping density that corresponds to.  arly mark (underline or box) your answers.  cify the units on answers whenever appropriate.					
	SCORE:1/20					
	2/ 15					
	3/ 15					
	Total /50					

## PHYSICAL CONSTANTS

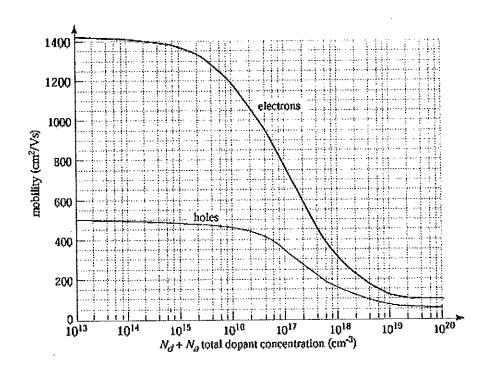
<u>Description</u>	<u>Symbol</u>	<u>Value</u> PROPERTIES OF SILICON AT 300K			
Electronic charge	$\overline{q}$	1.6×10 <sup>-19</sup> C	<u>Description</u>	<u>Symbol</u>	<u>Value</u>
Boltzmann's constant	$\bar{k}$	8.62×10 <sup>-5</sup>	Band gap energy	$E_{\mathbf{G}}$	1.12 eV
		eV/K	Intrinsic carrier	$n_{\rm i}$	$10^{10}  \mathrm{cm}^{-3}$
Thermal voltage at	$V_{\mathrm{T}} =$	0.026 V	concentration		10
300K	kT/q		Dielectric permittivity	$arepsilon_{ ext{Si}}$	$1.0 \times 10^{-12}$
2 0 0 2 2					F/cm

## **USEFUL NUMBERS**

 $V_T \ln(10) = 0.060 \text{ V} \text{ at } T=300 \text{K}$ 

Depletion region Width: 
$$W = \sqrt{\frac{2\varepsilon}{q} \left( \frac{1}{N_a} + \frac{1}{N_d} \right) \left( V_{bi} - V_{Applied} \right)}$$

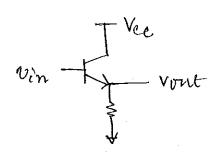
## Electron and Hole Mobilities in Silicon at 300K



### Prob 1. [20]

(a) [8 pt] Say, we want a high input resistance and low output resistance amplifier. There is no requirement on the gain. Which amplifier topology will you use? By using a small signal model, derive the input and output resistance of this amplifier. You could use the simplest configuration of the amplifier for your analysis.

common collector or emitter follower



un Q  $q_m v_n = \beta i_b$   $q_m v_n = \beta i_b$ 

$$R'n = \frac{V'n}{r'b} = \gamma_{tt} + (\beta+1) P_{E}$$

Rout = 
$$R_E II \frac{V_X}{I'}$$

$$V_{X} = -V_{T}$$

$$V'_{X} = -(B+1) \frac{V_{P}}{V_{P}} = -(B+1) \frac{V_{P}}{V_{P}}$$

$$V_{Y} = \frac{V_{Y}(B+1)}{V_{P}}$$

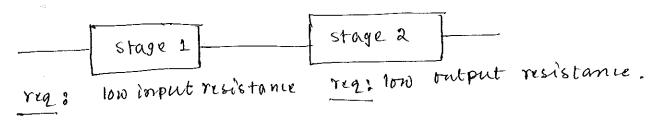
$$V_{Y} = \frac{V_{Y}(B+1)}{V_{P}}$$

$$\frac{V_{X}}{I} = \frac{Y_{fc}}{\beta + 1} \approx \frac{1}{g_{m}}$$

$$\frac{1}{1} = \frac{V_{gm}}{\beta + 1} \approx \frac{1}{g_{m}}$$

(b)[8 pt] Now consider a problem where we need a circuit that gives (i) low input resistance (ii) low output resistance and (iii) high amplitude of the gain. The sign of the gain is not important. How will you design such a circuit? Note that, you are free to use more than one transistor in your design. Make sure you adequately explain your circuit.

Ne can design a two stage circuit

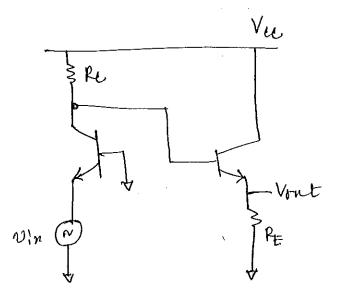


We note that total gain, Av = Av, X Av\_

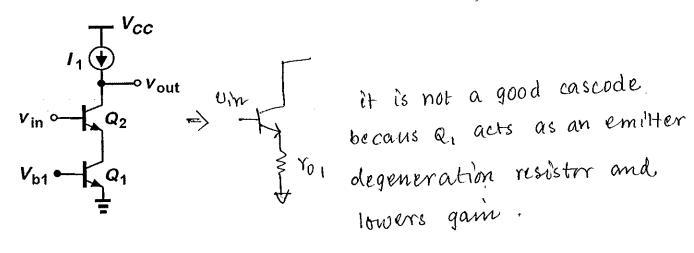
Thus if one of the stages has high gain, all the requirements can be satisfied.

Then: Stage 1: CB (low imput resistance é mish gain)
Stage 2: Cc (low output resistance é Aux1)

can be chosen.

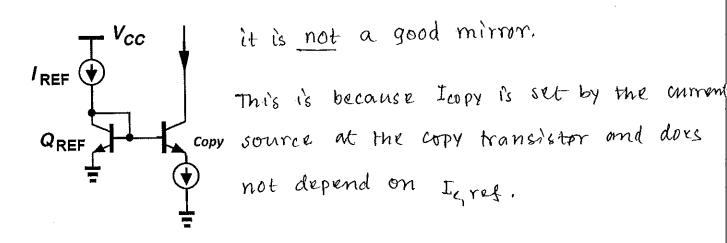


(c) [4 pt] Is the following a good cascode? Qualitatively explain why or why not.

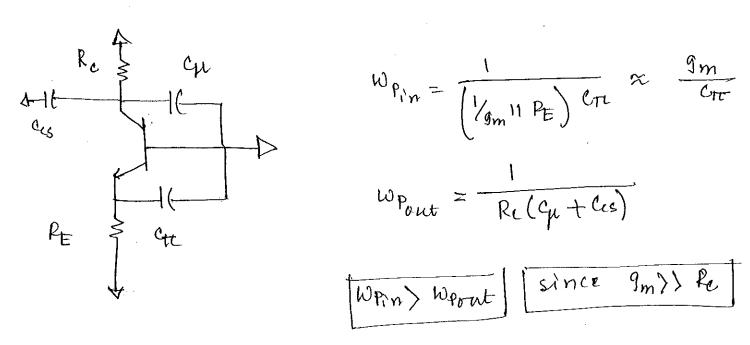


## Prob 2 [15 pt]

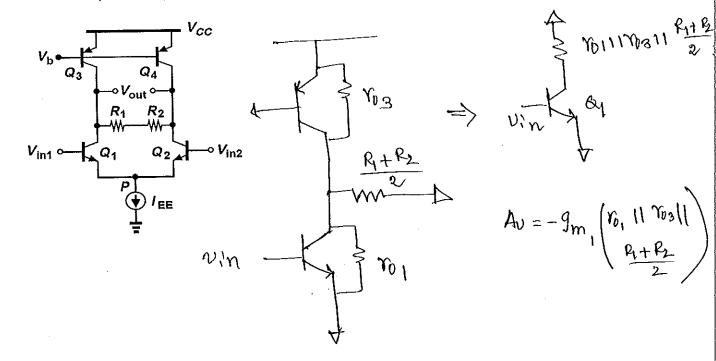
(a) [4 pt] Is the following a good current mirror? Qualitatively explain why or why not? Note that the current source on the copy transistor is NOT a golden current source.



(b) [6 pt] For a common base amplifier, find out the input and output pole frequencies. Which one is expected to be larger?



(c)[5 pt] Find out the gain of the following amplifier when  $R_1$  and  $R_2$  are NOT equal. Also consider Early effect in your analysis.

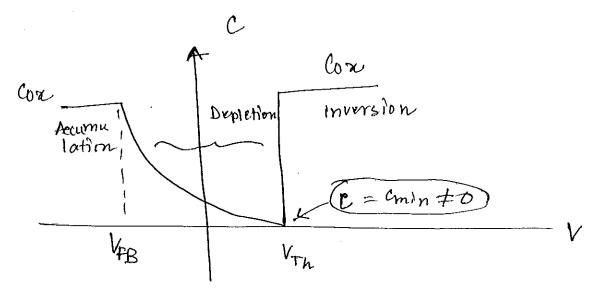


Prob 3. [15 pt]

## (a) [5 pt]

Condition	True	False
A MOSFET with p-type body will have p+ source and drain		<u> </u>
The doping of the body and the polysilicon gate are of the same type		
Between two gate oxides, the one with the higher permittivity is preferred	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	
The pinch-off region looks like a reverse biased p-n junction	V	
Channel length modulation becomes more prominent for shorter channel length devices	~	

(b)[4 pt] For a p-body MOS capacitor, draw the C-V plot clearly showing the different regions of operation and also the flatband and threshold voltages.



(c) [6 pt]

(i) [2 pt] Write down the different charges present in the channel at inversion. Do all these charges contribute to current flow? Why or why not?

(ii) [1 pt] Write down a mathematical expression for the charge density per unite area that provides current in the inversion region as a function of gate voltage.

(iii)[3 pt] Starting from I=WQv, where W is the width of the transistor, Q is the charge density per unit area and v is the velocity of electrons, find out the expression for current in a velocity saturated MOSFET. From an experimental measurement, how will you say that the MOSFET is indeed velocity saturated?

(i) immobile depletion charge mobile inversion charge

$$(i)$$
  $Q = Cox (Vgs - Vtn)$ 

For velocity saturated mosfet ID changes lineary with Vg.

For a conventional MOSFET, Ion Vg2